

AZ 5214E – run sheet

MicroChemicals / Merck Performance Materials GmbH

[nanyte.com/photoresists/az-5214e](https://www.merck.com/nanyte.com/photoresists/az-5214e) · last updated 2026-07-26

Thickness: 1.1–2.0 µm

Softbake: 110 °C · 50 s · hotplate

Post-exposure bake: 120 °C (115–125 °C) · 2 min

Flood exposure: 200 mJ/cm²

Develop: Developer AZ 340 (metal-ion-containing) or AZ 726 MIF (metal-ion-free) · Dilution AZ 340 used 1:5 diluted; AZ 726 MIF used as supplied · Method AZ 340: tank or spray; AZ 726 MIF: puddle

Hardbake: 120 °C · 50 s